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(54) Title: SLURRY AND/OR CHEMICAL BLEND SUPPLY APPARATUSES

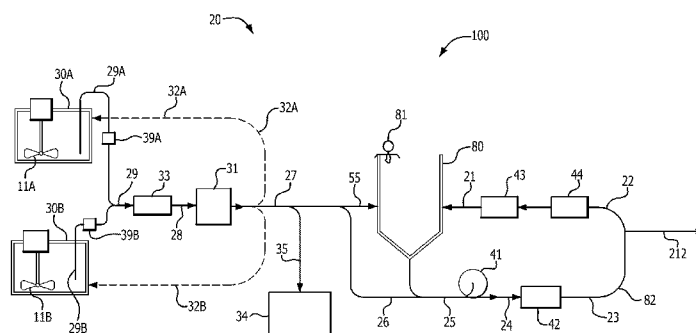


FIG. 1A

(57) Abstract: A slurry and/or chemical blend supply apparatus suitable for providing slurry and/or chemical blend to chemical mechanical planarization (CMP) tools or other tools in a semiconductor fabrication facility, related processes, methods of use and methods of manufacture. The slurry and/or chemical blend supply apparatus includes one or more of the following: feed module, blend module, analytical module and distribution module.